



## *EE141-Spring 2009 Digital Integrated Circuits*

Lecture 3  
Metrics (Cntd)  
IC Manufacturing

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### *Administrativa*

- ❑ Discussions start this week (Tomorrow)
- ❑ TA office hours will be held in 514 Cory
- ❑ Labs start next week
  - Everyone should have an EECS instructional account
  - You should have card key access to 353 Cory be now
- ❑ Concerns about discussion session
- ❑ Homework #1 is due this Friday
- ❑ Homework #2 to be posted on Friday

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## *Class Material*

- ❑ Last lecture
  - Basic metrics for IC design (Started)
- ❑ Today's lecture
  - Metrics Continued
  - Design Rules
- ❑ Reading (1, 2.2, A)

## *Review: Cost*

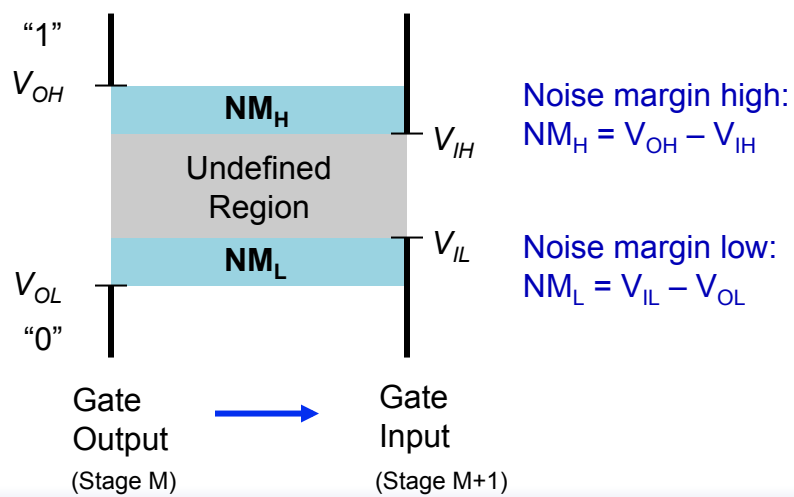
## Review: Reliability

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## Definition of Noise Margins



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## Key Reliability Properties

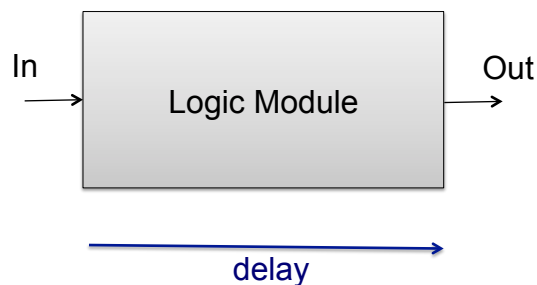
- ❑ Absolute noise margin values are not the only things that matter
  - e.g., floating (high impedance) nodes are more easily disturbed than low impedance nodes (in terms of voltage)
- ❑ Noise immunity (i.e., how well the gate suppresses noise sources) needs to be considered too
- ❑ Summary of some key reliability metrics:
  - Noise transfer functions & margin (ideal: gain =  $\infty$ , margin =  $V_{dd}/2$ )
  - Output impedance (ideal:  $R_o = 0$ )
  - Input impedance (ideal:  $R_i = \infty$ )

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## Primary Performance Metric: Delay



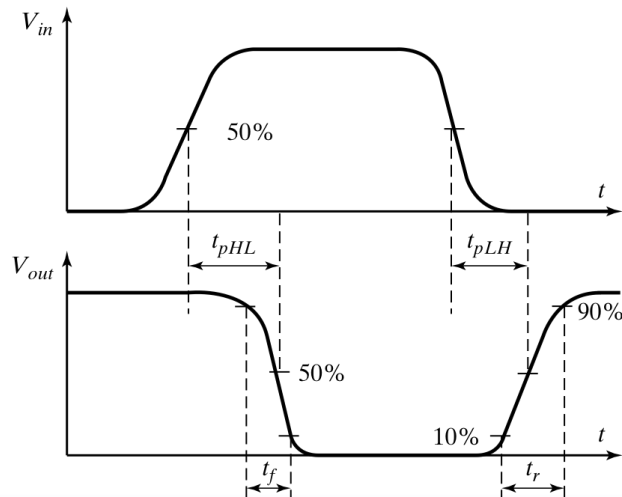
*How to define delay in a universal way?*

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## Delay Definitions



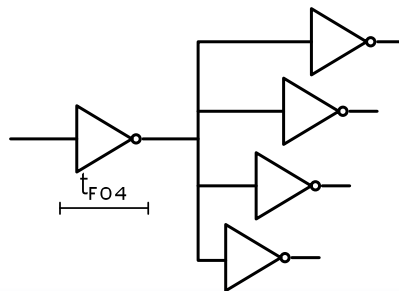
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## Fanout of Four (FO4) Delay

- Want a way to characterize the delay of a circuit (roughly) independent of environment
- Most common metric:
  - Delay of an inverter driving four copies of itself ( $t_{FO4}$ )

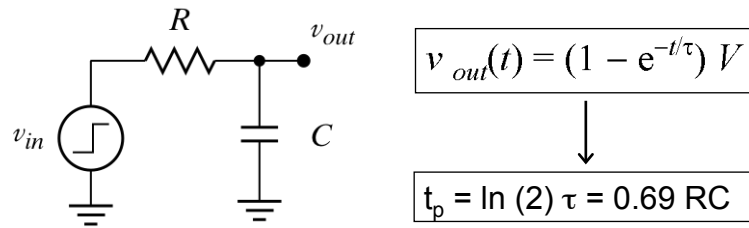


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## A First-Order RC Network



**Important model – matches delay of an inverter**

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## Power Dissipation

Instantaneous power:

$$p(t) = v(t)i(t) = V_{supply}i(t)$$

Peak power:

$$P_{peak} = V_{supply}i_{peak}$$

Average power:

$$P_{ave} = \frac{1}{T} \int_t^{t+T} p(t) dt = \frac{V_{supply}}{T} \int_t^{t+T} i_{supply}(t) dt$$

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## *“Power-Delay” and Energy-Delay*

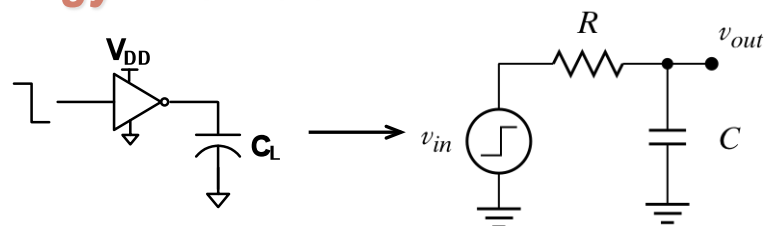
- ❑ Want low power and low delay, so how about optimizing the product of the two?
  - So-called “Power-Delay Product”
- ❑ Power-Delay is by definition Energy
  - Optimizing this pushes you to go as slow as possible
- ❑ Alternative gate metric: Energy-Delay Product
  - $EDP = (P_{av} \cdot t_p) \cdot t_p = E \cdot t_p$

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## *Energy in CMOS*



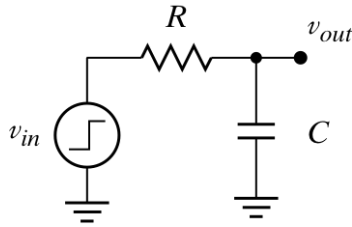
- ❑ The voltage on  $C_L$  eventually settles to  $V_{DD}$
- ❑ Thus, charge stored on the capacitor is  $C_L V_{DD}$ 
  - This charge has to flow out of the power supply
- ❑ So, energy is just  $Q \cdot V_{DD} = (C_L V_{DD}) \cdot V_{DD}$

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## Energy (the harder way)



$$E_{0 \rightarrow 1} = \int_0^T P_{DD}(t) dt = V_{DD} \int_0^T i_{DD}(t) dt = V_{DD} \int_0^{V_{DD}} C_L dv_{out} = C_L V_{DD}^2$$

$$E_C = \int_0^T P_C(t) dt = \int_0^T v_{out} i_L(t) dt = \int_0^{V_{DD}} C_L v_{out} dv_{out} = \frac{1}{2} C_L V_{DD}^2$$

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## Summary

- Understanding the design metrics that govern digital design is crucial
  - Cost
  - Robustness
  - Performance/speed
  - Power and energy dissipation

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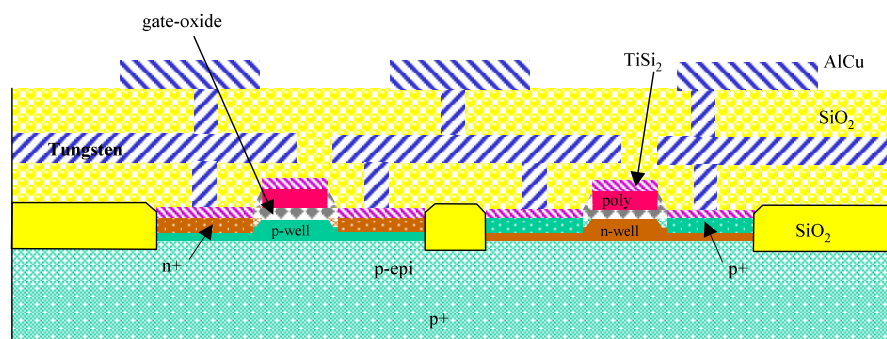
## Intermezzo: Design Rules

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## A Modern CMOS Process



## Dual-Well Shallow-Trench-Isolated CMOS Process

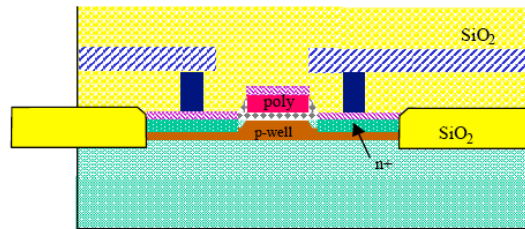
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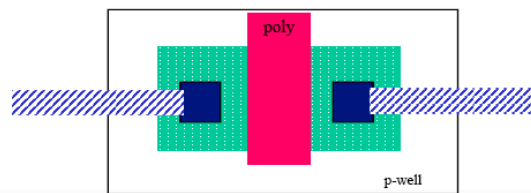
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## Transistor Layout

Cross-Sectional View



Layout View



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## CMOS Process Layers



















Layer	Color	Representation
Well (p,n)	Yellow	
Active Area (n+,p+)	Green	
Well contact (p+,n+)	Green	
Polysilicon	Red	
Metal1	Blue	
Metal2	Magenta	
Contact To Poly	Black	
Contact To Diffusion	Black	
Via	Black	

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## Layers in 0.25 $\mu\text{m}$ CMOS process

Layer Description	Representation				
metal					
	m1	m2	m3	m4	m5
well					
	nw				
polysilicon					
	poly				
contacts & vias					
	ct	v12,v23,v34,v45	mwc	pwc	
active area and FETs					
	ndif	pdif	nfct	pfct	
select (well contacts)					
	nplus	pplus	prb		

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## Design Rules

- ❑ Interface between designer and process engineer
- ❑ Guidelines for constructing process masks
- ❑ Unit dimension: Minimum line width
  - scalable design rules: lambda parameter
  - absolute dimensions (micron rules)

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## Design Rules

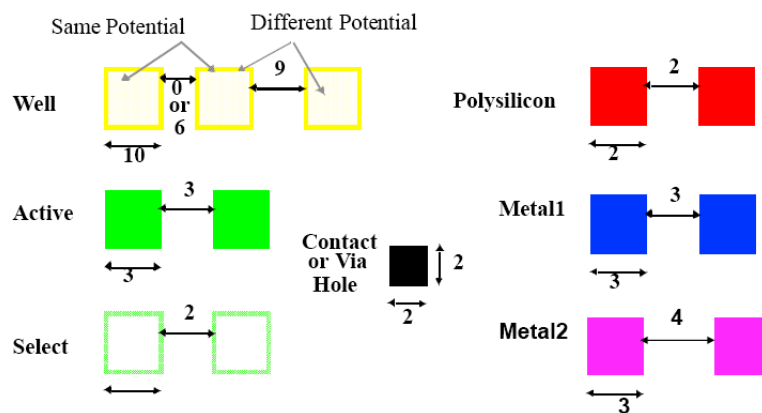
- Intra-layer
  - Widths, spacing, area
- Inter-layer
  - Enclosures, distances, extensions, overlaps
- Special rules (sub-0.25 $\mu\text{m}$ )
  - Antenna rules, density rules, (area)

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## Intra-Layer Design Rules

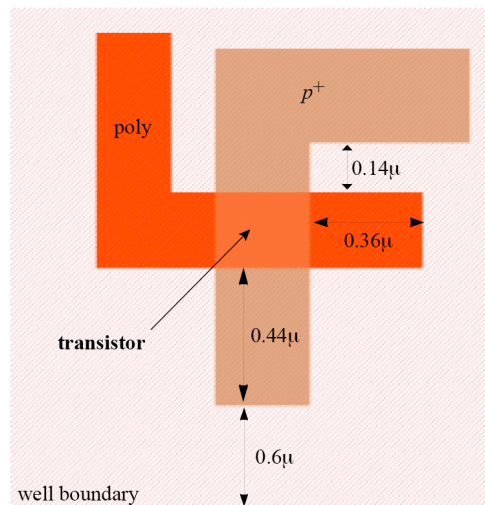


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## Inter-Layer: Transistor Layout

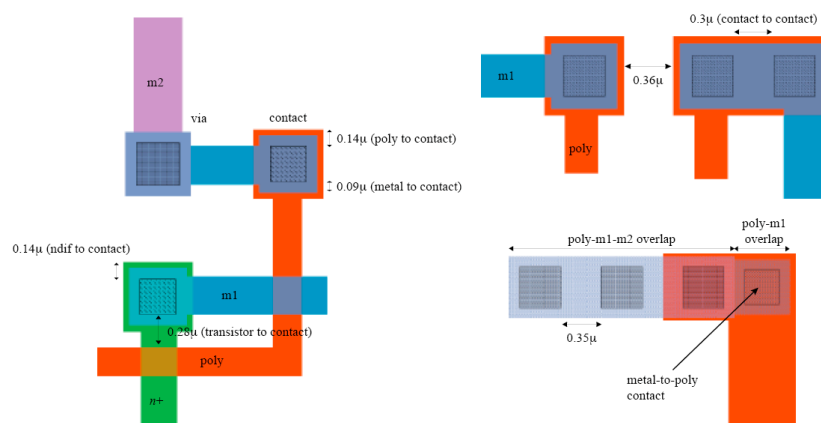


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## Inter-Layer: Vias and Contacts

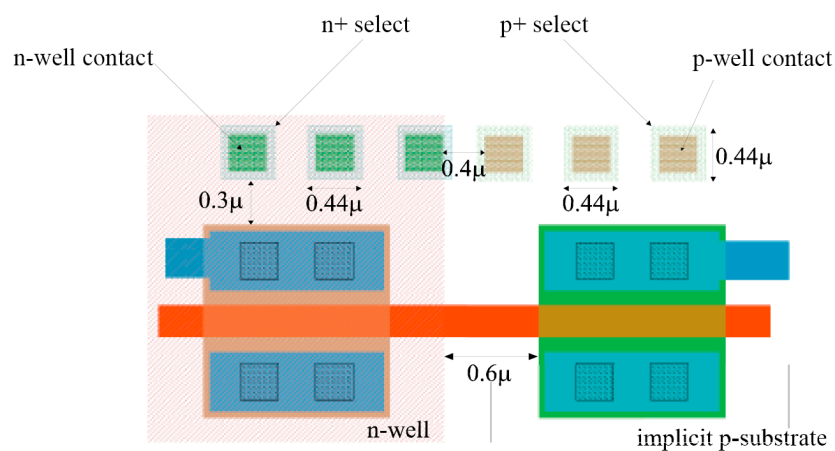


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## Inter-Layer: Well and Substrate

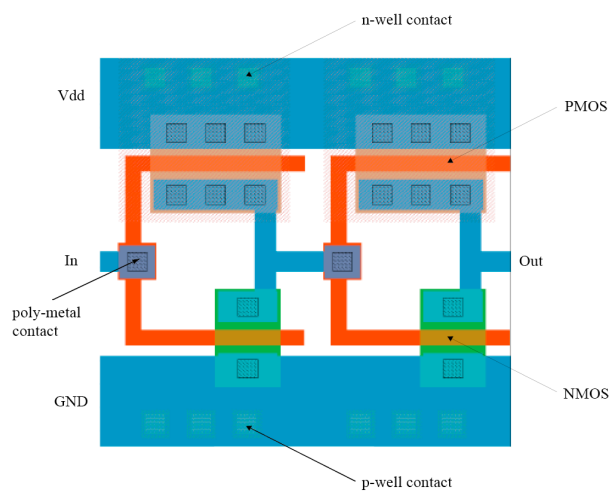


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## CMOS Inverter Layout

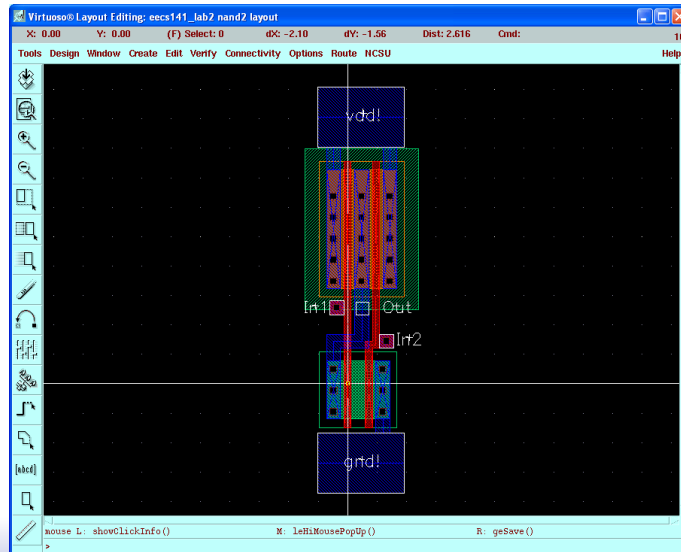


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## Layout Editor

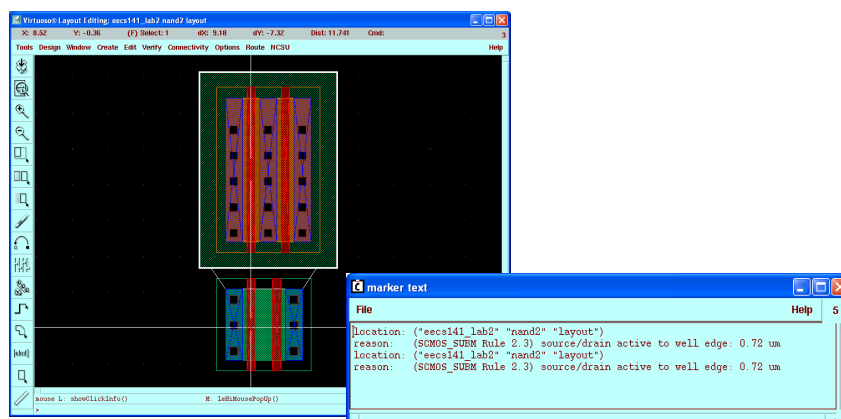


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## Design Rule Checker

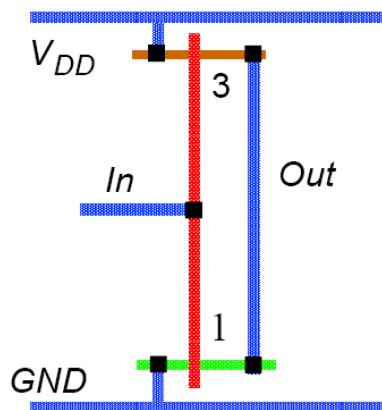


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## Sticks Diagram



- Dimensionless layout entities
- Only topology is important

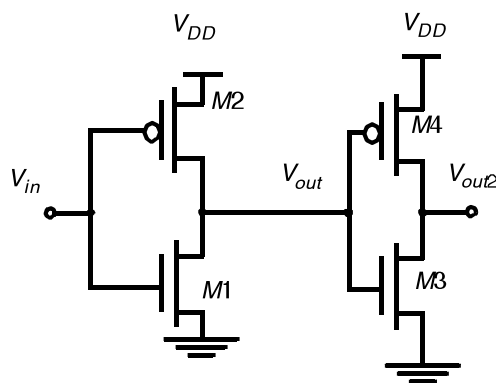
Stick diagram of inverter

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## Circuit Under Design



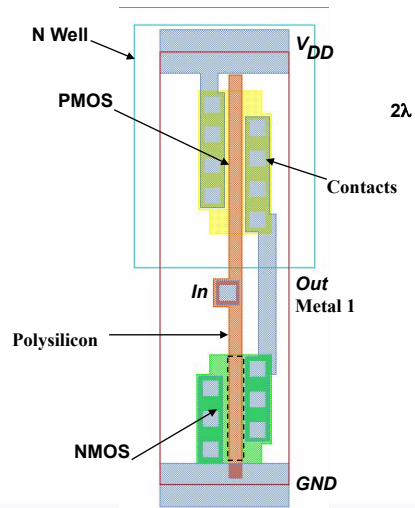
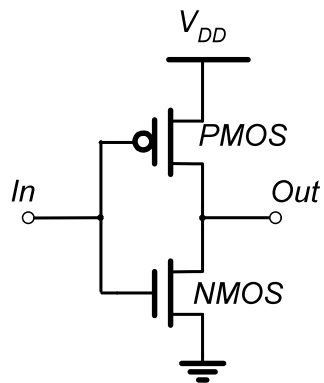
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## CMOS Inverter

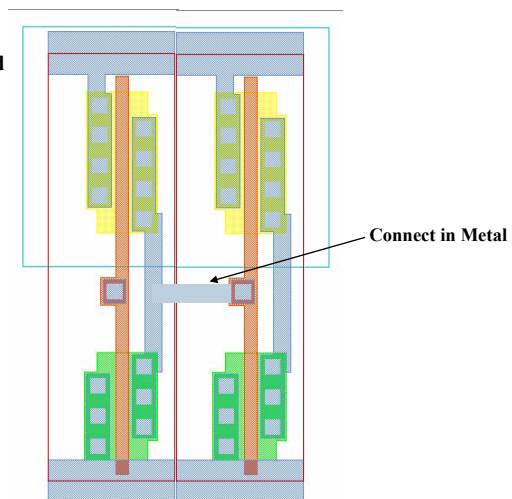
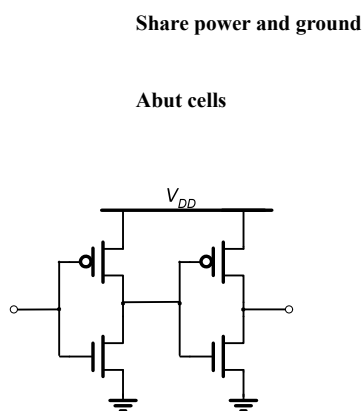


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## Two Inverters



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## *Next Lecture*

- From simple to more complex gates ...